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1030nm, 0.80 NA, aplanoXX Aplan Objective | aplanoXX NA0.8_20_1030

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AdlOptica aplanoXX Aplan Objectives



Stock #19-491 **1 In Stock**

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General

aplanoXX NA0.8_20_1030 **Model Number:**

Objective **Type:**

±0.3 **Field of View (°):**

Note:

Includes aplanoXX objective, mounted protective window (#19-495), and spanner wrench (#19-497)

Physical & Mechanical Properties

Length (mm):

54.10

Clear Aperture CA (mm):

20

Diameter (mm):

44.00

Optical Properties

Focal Length FL (mm):

12.50

Numerical Aperture NA:

0.80

Working Distance (mm):

2.5 (1.6 with Protective Window)

Design Wavelength DWL (nm):

1030

Wavelength Range (nm):

1020 - 1100

Damage Threshold, By Design: □

100 mJ @ 5ns
300 μJ @ 1ps

Focusing Depth (mm):

0 - 4

Beam Diameter (mm):

20 (maximum)

Damage Threshold, Pulsed:

100 mJ @ 5ns
300 μJ @ 1ps

Threading & Mounting

Mount:

C-Mount

Regulatory Compliance

RoHS 2015:

Compliant

Certificate of Conformance:

[View](#)

Reach 250:

Compliant

Country of Origin:

Germany

Imported By:

Edmund Optics India Private Limited

Product Details

- Aplanatic Optical Design
- High Numerical Aperture for Small Spot Sizes
- Designs for 800 and 1030nm with Focusing Depth Up to 4mm
- [AdlOptica foXXus Multi-Focus Objectives](#) Also Available

AdlOptica aplanoXX Aplan Objectives compensate for spherical aberration and coma when focusing into glass, sapphire, silicon carbide, silicon, PMMA, and other transparent materials at depths up to 4mm. These objectives are designed to be used with ultrafast solid-state and fiber lasers and are optimized for 800nm (Ti:sapphire) and 1030nm (Yb:doped). Featuring C-Mount threading and an optical design insensitive to misalignment, these objectives are easy to integrate into laser systems. AdlOptica aplanoXX Aplan Objectives are ideal for micromachining glass, 3D nanofabrication, waveguide recording, and selective laser etching. A collar on the objective allows for manual adjustment of focus and a replaceable front window protects from debris during materials processing.

Technical Information



